

## Electron Source for RHEED

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### Products

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    - > **RHEED-12**
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  - > Specialized RHEED Systems
    - > RHEED Accessories
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- > AUGER / XPS / EELS / REELS
- > Electron Sources
- > Ion Sources
- > X-ray Source
- > Energy Analyzers & Imaging Energy Filters

## RHEED-12

RHEED guns from STAIB Instruments provide unique electron optics systems for diffraction studies. RHEED-12 features full electrostatic electron optics and electrostatic beam deflection. The source is  $\mu$  metal shielded.

### Key features

- Energy range 500 eV to 12 keV
- Beam current (max.) 30  $\mu$ A
- Beam size (min.) 100  $\mu$ m at low current and 150 mm WD and max. energy

### Characteristics

- Working distance 50 mm – 500 mm
- [Basic beam blanking](#)
- [Beam blanking, external \(optional\)](#)
- [Computer control \(optional\)](#)
- Remote control

### Typical Applications

[MBE](#)  
[Cathodoluminescence](#)



Not all parameters can be reached simultaneously. Above specifications may change without notice. Pictures / diagrams for reference only.

### Related Products

[Fluorescent screens](#)  
[Screen shutters](#)  
[Magnetic shielding for the beam path](#)  
[Filaments](#)  
[Pre-mounted, pre-aligned cathode units](#)

- > Charged Particle Detectors
- > PEEM & IEEM
- > UHV-Systems for Surface Analysis
- > Packages for Surface Analysis
- > Data Acquisition & Instrument Control Software

- X-ray shielding glass covers
- Complete service kit
- Diagnostic box
- RHEED data acquisition & data analysis package
- STAIB Computer Control Module
- RHEED imaging analyzer
- RHEA100
- In-situ* AugerProbe™

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## APPLICATIONS

- > *In situ* Characterization
- > Surface Analysis Techniques
- > Material Growth Monitoring
- > Electron Diffraction
- > Scanning Electron Microscopy
- > Photoelectron Microscopy (PEEM)
- > Depth Profiling
- > Space Environment Simulation
- > Surface & Materials Modification

## STAIB INSTRUMENTS

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